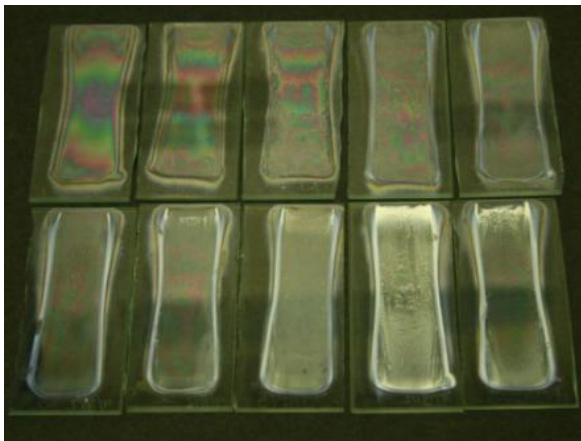


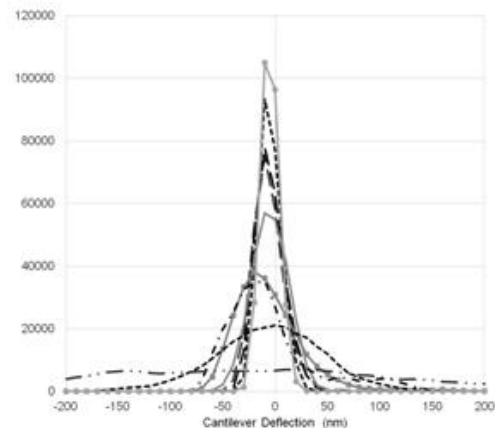
Developed by Prof. David Sheel and Dr John Hodgkinson, Materials Group

This improved technology applies advances in plasma generation to extend the capability of plasma-enhanced chemical vapour deposition (CVD) and etching processes at atmospheric pressure.

- Controllable, highly-activated plasma enables 3D nano-structuring of surfaces
 - Control of etch and/or deposition rate
 - Manipulation of surface structure, crystallinity, composition etc.
 - Enables processing of substrates at substantially reduced temperatures
- Potentially enables:
 - Treatment of thermally sensitive substrates e.g. plastics, composites
 - Removal of wet chemistry-based techniques in manufacture
 - Online, controllable processing for one or both sides of substrate
 - Potential for the deposition of novel materials
- Highly scalable, low capital cost infrastructure for process technology



Titania films deposited on glass substrates



AFM profiles of etched ZnO films

Seeking:

Commercial partnership for further technology development and route to market, with option of exclusive rights to license the technology.

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